

IN THE CLAIMS

Please amend the claims as follows:

1 to 18. (canceled).

19. (previously presented) A process for producing rotationally symmetrical quartz glass crucibles, said process comprising:

creating an electric arc by means of an electrode arrangement comprising one or several anodes and a cathode so as to heat a wall, or a section thereof, of the rotating quartz glass crucible;

creating an additional electric arc heating an additional wall section of the quartz glass crucible by means of at least one additional electrode arrangement comprising one or more anodes and a cathode.

20. (previously presented) A process according to Claim 19, wherein the electrode arrangement heats different sections located at a distance from one another in a direction of a rotational axis of the quartz glass crucible.

21. (currently amended) A process according to Claim 19, wherein [device for producing a rotationally symmetrical quartz glass crucible, said device comprising:

~~a first electrode arrangement for zone-by-zone heating of the quartz glass crucible on a structure supporting the quartz glass crucible rotatably about a rotational axis, said first electrode arrangement creating an electric arc and comprising one or more anodes and a cathode;]~~

the additional ~~[a second]~~ electrode arrangement ~~[comprising one or more anodes and a cathode and]~~ is inclined toward a section of the quartz glass crucible opposite the first electrode arrangement.

22. (currently amended) A process ~~[device]~~ according to Claim 19 ~~[24]~~, wherein the electrode arrangements are located in different positions at a distance from one another in the direction of the rotational axis of the quartz glass crucible.

23. (currently amended) A process ~~[device]~~ according to Claim 19 ~~[24]~~, wherein the electrode arrangements are displaceable independently from one another.

24. (currently amended) A process ~~[device]~~ according to Claim 22, wherein the electrode arrangements are displaceable independently from one another.

25. (currently amended) A process ~~[device]~~ according to Claim 19 ~~[24]~~, wherein the electrode arrangements are evenly spaced in relation to a periphery of the quartz glass crucible.

26. (currently amended) A process ~~[device]~~ according to Claim 22, wherein the electrode arrangements are evenly spaced in relation to a periphery of the quartz glass crucible.

27. (currently amended) A process ~~[device]~~ according to Claim 23, wherein the electrode arrangements are evenly spaced in relation to a periphery of the quartz glass crucible.

28. (currently amended) A process [device] according to Claim 24, wherein the electrode arrangements are evenly spaced in relation to a periphery of the quartz glass crucible.

29. (currently amended) A process [device] according to Claim 19 [21] wherein at least one of the electrode arrangements [electrode arrangement] is provided with a supply apparatus supplying SiO₂ granulate, and at least one additional electrode arrangement is provided exclusively for heating.

30. (currently amended) A process [device] according to Claim 22 wherein at least one of the electrode arrangements [electrode arrangement] is provided with a supply apparatus supplying SiO₂ granulate, and at least one additional electrode arrangement is provided exclusively for heating.

31. (currently amended) A process [device] according to Claim 23 wherein at least one of the electrode arrangements [electrode arrangement] is provided with a supply apparatus supplying SiO₂ granulate, and at least one additional electrode arrangement is provided exclusively for heating.

32. (currently amended) A process [device] according to Claim 24 wherein at least one of the electrode arrangements [electrode arrangement] is provided with a supply apparatus supplying SiO₂ granulate, and at least one additional electrode arrangement is provided exclusively for heating.

33. (currently amended) A process [device] according to Claim 25 wherein at least one of the electrode arrangements [electrode arrangement] is provided with a supply

apparatus supplying SiO₂ granulate, and at least one additional electrode arrangement is provided exclusively for heating.

34. (currently amended) A process [~~device~~] according to Claim 26 wherein at least one of the electrode arrangements [~~electrode arrangement~~] is provided with a supply apparatus supplying SiO₂ granulate, and at least one additional electrode arrangement is provided exclusively for heating.

35. (currently amended) A process [~~device~~] according to Claim 27 wherein at least one of the electrode arrangements [~~electrode arrangement~~] is provided with a supply apparatus supplying SiO₂ granulate, and at least one additional electrode arrangement is provided exclusively for heating.

36. (currently amended) A process [~~device~~] according to Claim 28 wherein at least one of the electrode arrangements [~~electrode arrangement~~] is provided with a supply apparatus supplying SiO₂ granulate, and at least one additional electrode arrangement is provided exclusively for heating.